CLAIMS

1. A microcrystalline glass, wherein the microcrystalline glass comprises a lithium disilicate crystalline phase, wherein the lithium disilicate crystalline phase has a higher weight percentage than other crystalline phases present in the microcrystalline glass;

in terms of molar percentage of oxides, the microcrystalline glass comprises components as follows: SiO_2: 61.50%–63.40%, Al_2O_3: 2.75%–2.99%, P_2O_5: 0.91%–1.91%, ZrO_2: 4.20%–4.85%, Na_2O: 1.80%–3.20%, B_2O_3: 0–1.00% and Li_2O: 25.32%–26.52%; and

in composition of the microcrystalline glass, a molar percentage $[Na_2O]$ of Na_2O, a molar percentage $[B_2O_3]$ of B_2O_3 and a molar percentage $[ZrO_2]$ of ZrO_2 satisfy a following relationship:

$Z=-1.344\times(2.65-100\times[Na_2O])^2+0.466\times100\times[B_2O_3]+1.203\times100\times[ZrO_2]$, where $4.98\leq Z\leq5.35$,

at a thickness of 0.70 mm, a b value of the microcrystalline glass is <0.70.

2. The microcrystalline glass according to claim 1, wherein $4.98\leq Z\leq5.20$.

3. The microcrystalline glass according to claim 1, wherein in the composition of the microcrystalline glass, the molar percentage $[Na_2O]$ of Na_2O and the molar percentage $[B_2O_3]$ of B_2O_3 satisfy a following relationship:

$0.90\%\leq[Na_2O]-[B_2O_3]\leq3.10\%$.

4. The microcrystalline glass according to claim 1, wherein in the composition of the microcrystalline glass, the molar percentage $[Na_2O]$ of Na_2O and the molar percentage $[Li_2O]$ of Li_2O satisfy a following relationship:

$8.55\leq[Li_2O]/[Na_2O]\leq13.85$.

5. The microcrystalline glass according to claim 4, wherein in the composition of the microcrystalline glass, the molar percentage $[Na_2O]$ of Na_2O and the molar percentage $[Li_2O]$ of Li_2O satisfy a following relationship:

$8.55\leq[Li_2O]/[Na_2O]\leq11.50$.

6. The microcrystalline glass according to any one of claims 1–5, wherein the lithium disilicate crystalline phase accounts for 70% or more by weight of all crystalline phases of the microcrystalline glass.

7. The microcrystalline glass according to any one of claims 1–5, wherein in terms of molar percentage of oxides, in the microcrystalline glass:

a molar percentage of SiO_2 is 61.50%–63.30%; and/or

a molar percentage of P_2O_5 is 1.20%–1.91%; and/or

the molar percentage of Na_2O is 1.85%–3.05%; and/or

the molar percentage of B_2O_3 is 0–0.65%; and/or

the molar percentage of ZrO_2 is 4.20%–4.80%; and/or

a molar percentage of Li_2O is 25.52%–26.52%.

8. The microcrystalline glass according to any one of claims 1–5, wherein crystallinity of the microcrystalline glass is not lower than 45%; and/or

in the microcrystalline glass, an average grain size is not larger than 100 nm.

9. The microcrystalline glass according to claim 1, wherein at a thickness of 0.70 mm, for light with a wavelength of 550 nm, transmittance of the microcrystalline glass is ≥90.00%.

10. The microcrystalline glass according to any one of claims 1–5, wherein Young's modulus of the microcrystalline glass is ≥100 GPa; and/or

Vickers hardness of the microcrystalline glass is ≥640 kgf/mm^2.

11. A chemically strengthened microcrystalline glass, wherein the chemically strengthened microcrystalline glass is fabricated from the microcrystalline glass according to any one of claims 1-10 through a chemical strengthening treatment, wherein composition at a center of the chemically strengthened microcrystalline glass or composition of a tensile stress layer is identical to that of the microcrystalline glass, the chemically strengthened microcrystalline glass comprises a compression stress layer region extending from a surface of the chemically strengthened microcrystalline glass to a compression depth, and a tensile stress exists inside the chemically strengthened microcrystalline glass.

12. The chemically strengthened microcrystalline glass according to claim 11, wherein the chemically strengthened microcrystalline glass has CT_LD of 45,000–55,000 MPa/mm, wherein the CT_LD is tensile stress linear density; and/or

the chemically strengthened microcrystalline glass has DOL_0 of 0.18 t–0.25 t, wherein the DOL_0 is a depth of the compression stress layer, and t is a thickness of the chemically strengthened microcrystalline glass; and/or

the chemically strengthened microcrystalline glass has CS_50 of 150–199 MPa, wherein the CS_50 refers to a compressive stress value at a depth of 50 μm from a main surface of the chemically strengthened microcrystalline glass; and/or

the chemically strengthened microcrystalline glass has |CT_AV| of 80–98 MPa, wherein the |CT_AV| is an absolute value of an average tensile stress; and/or

the chemically strengthened microcrystalline glass has |CT_CV| of 115–142 MPa, wherein the |CT_CV| is an absolute value of a maximum tensile stress.

13. The chemically strengthened microcrystalline glass according to any one of claims 11–12, wherein Vickers hardness of the chemically strengthened microcrystalline glass is larger than or equal to 680 kgf/mm^2.

14. The chemically strengthened microcrystalline glass according to claim 11, wherein a molten salt bath for the chemical strengthening treatment is a molten salt bath containing sodium salt and/or potassium salt, a temperature of the molten salt bath is 380 °C–470 °C, and the chemical strengthening treatment lasts for 0.1–3 h.

15. An electronic device, wherein the electronic device comprises the microcrystalline glass according to any one of claims 1–10 or the chemically strengthened microcrystalline glass according to any one of claims 11–14.